

# The 3D Silicon Leader

## High Density Silicon based Capacitors for Power Electronics System Integration

Powersoc ,November 2012

Catherine Bunel



# Outline

- Introduction
- 3D Silicon Capacitor density roadmap
- A new worldwide record of capacitor density
- High voltage capacitors
- Examples of applications
- Conclusion

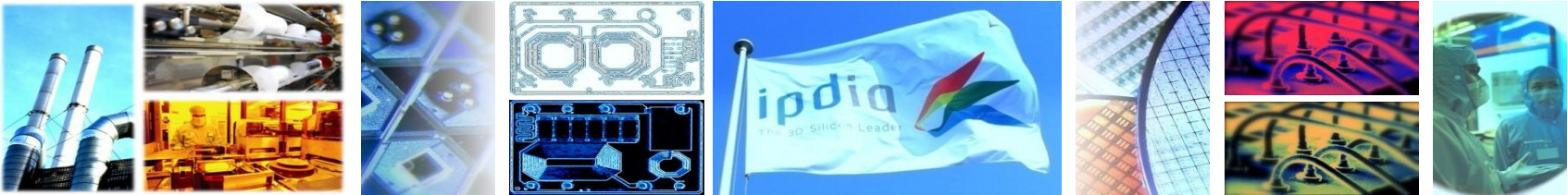


# Introduction



# Who are we?

- Independent Company located in Caen, Normandy, France
- Dedicated to manufacturing of leading edge Integrated Passive Devices
- 20 M\$ revenues, 100 people and operating own Silicon wafer fab
- Strong R&D team and collaborations with leading research institutes



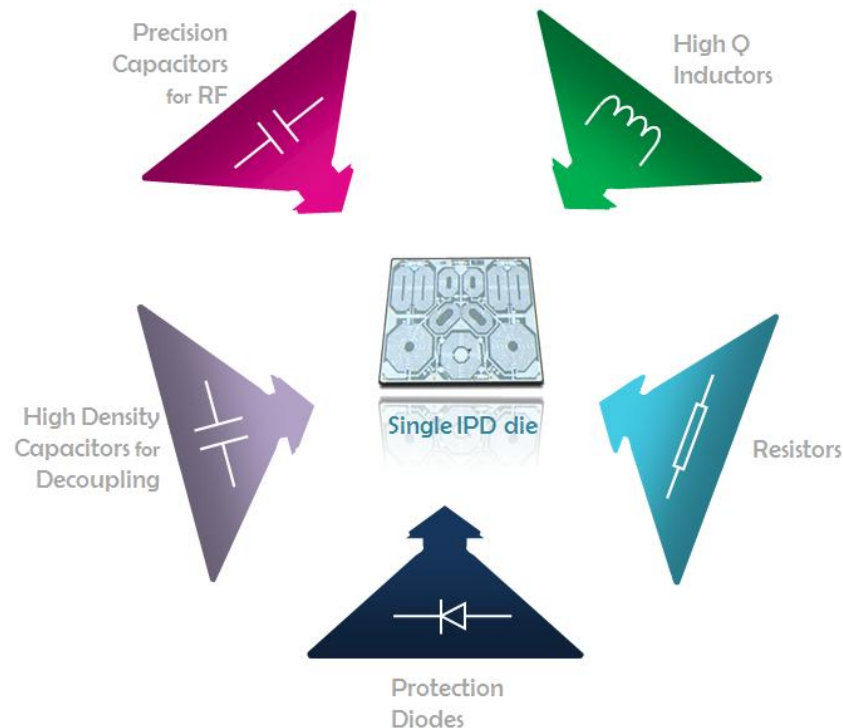
# What do we do?

**High performance, high stability and high reliability** silicon passive components to customers in communication, harsh environment, industrial, lighting, and medical markets.



# PICS-IPD, a Unique Technology

Passive Integration Connecting Substrate



Up to 100's of passive components can be integrated

Value proposition is:

- Size
- Cost
- Performance

# IPDIA value proposition: Technology that enables

- **Miniaturization of application**

- Module: High density integration
- High PCB area saving (e.g. > 40%)
- Silicon die with embedded passives as replacement of external SMD components
- Compatible with standard wire bonding or reflow assembly according to scenarios

- **Reduced Cost**

- BOM level
- Simpler manufacturing with module
- Simpler application with less components to place

- **Enhanced Performance**

- Very high stability vs temperature, -55°C to +210(\*)°C operating range
- High stability vs voltage, time...
- High reliability (no cracking & very low failure rate < 2ppm)
- Efficient decoupling with low ESR/ESL by full integration on silicon
- Lower battery life time with very low leakage current
- PCB influence cancelled

- **Greater Flexibility**

- One configurable IPD allowing a set of output voltages

(\*): limited by the active part, up to 250°C is possible with our passive integration

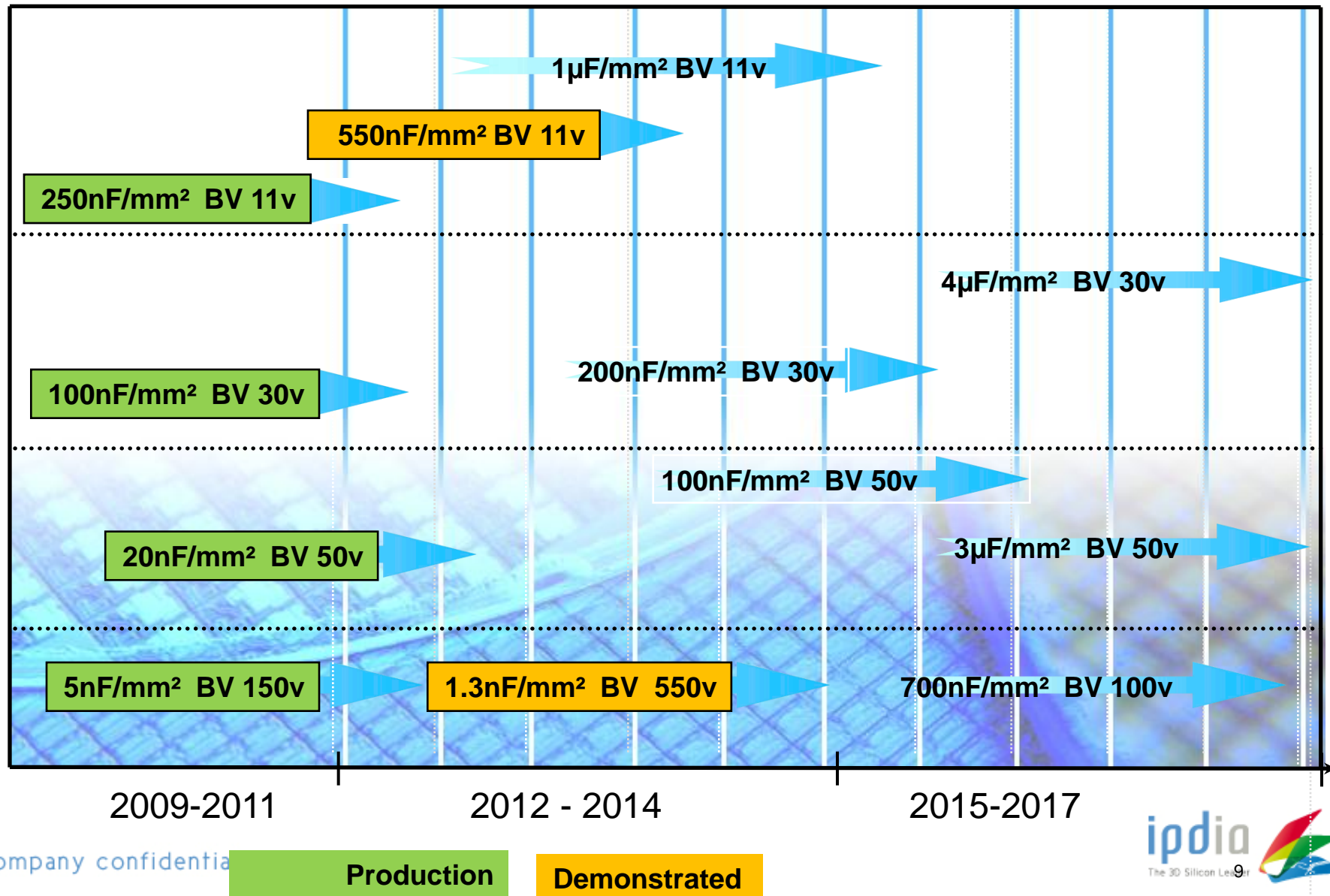





# **3D CAPACITOR DENSITY ROADMAP**



# 3D Capacitor Density Roadmap

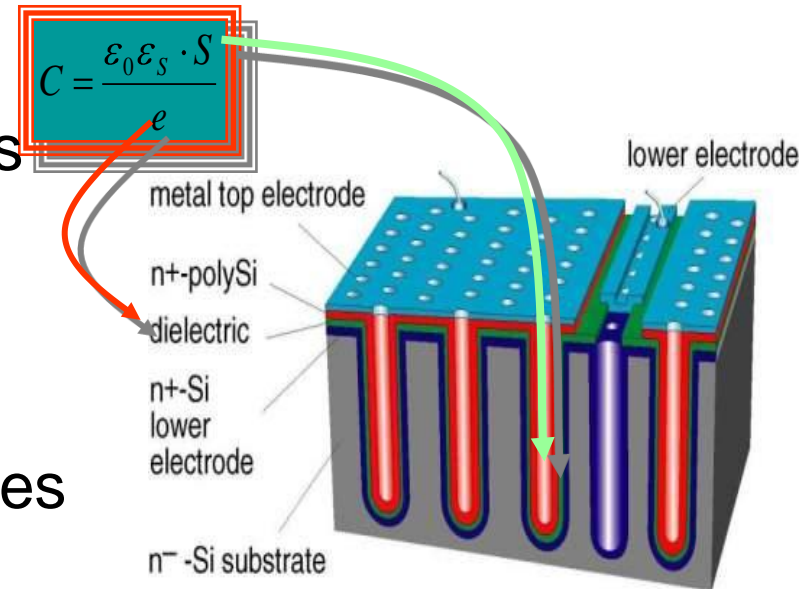




**PICS4=550nF/mm<sup>2</sup>  
A NEW  
WORLDWIDE  
RECORD**

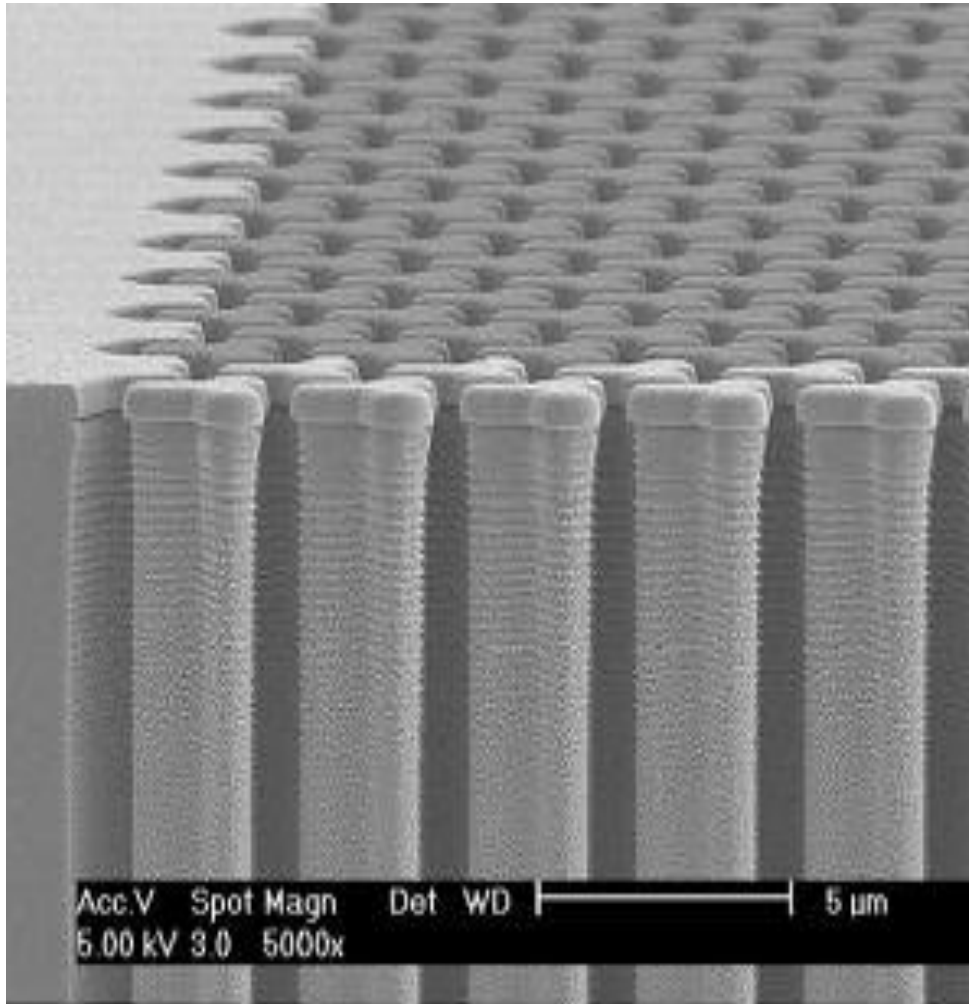
# Key features for highly integrated Capacitors

- Increase the effective capacitor surface by etching 3D structures with high aspect ratio.
- Suitable high k material with appropriate deposition techniques
  - High permittivity
  - High breakdown voltage > 10V
  - Low leakage current < 1nA/μF
  - Excellent temperature and voltage linearity < 100ppm/°K & < 100ppm/V
  - Failure in Time < 1





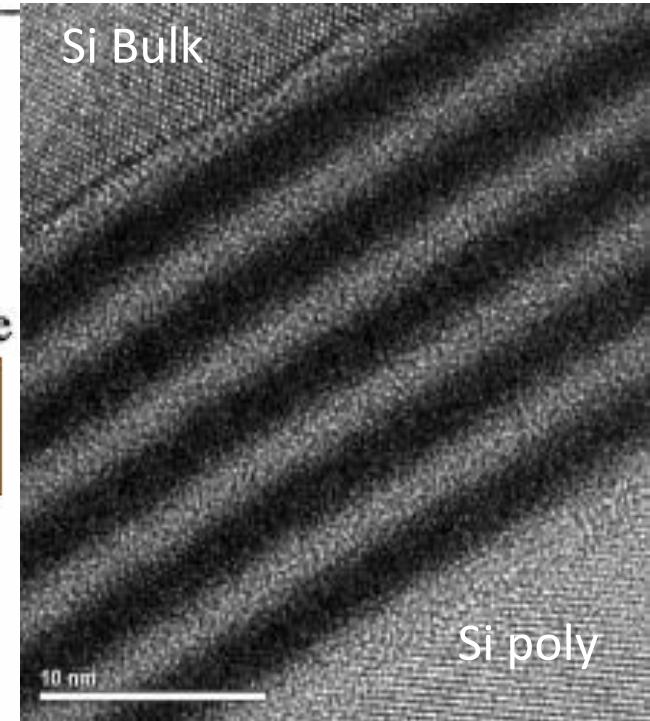
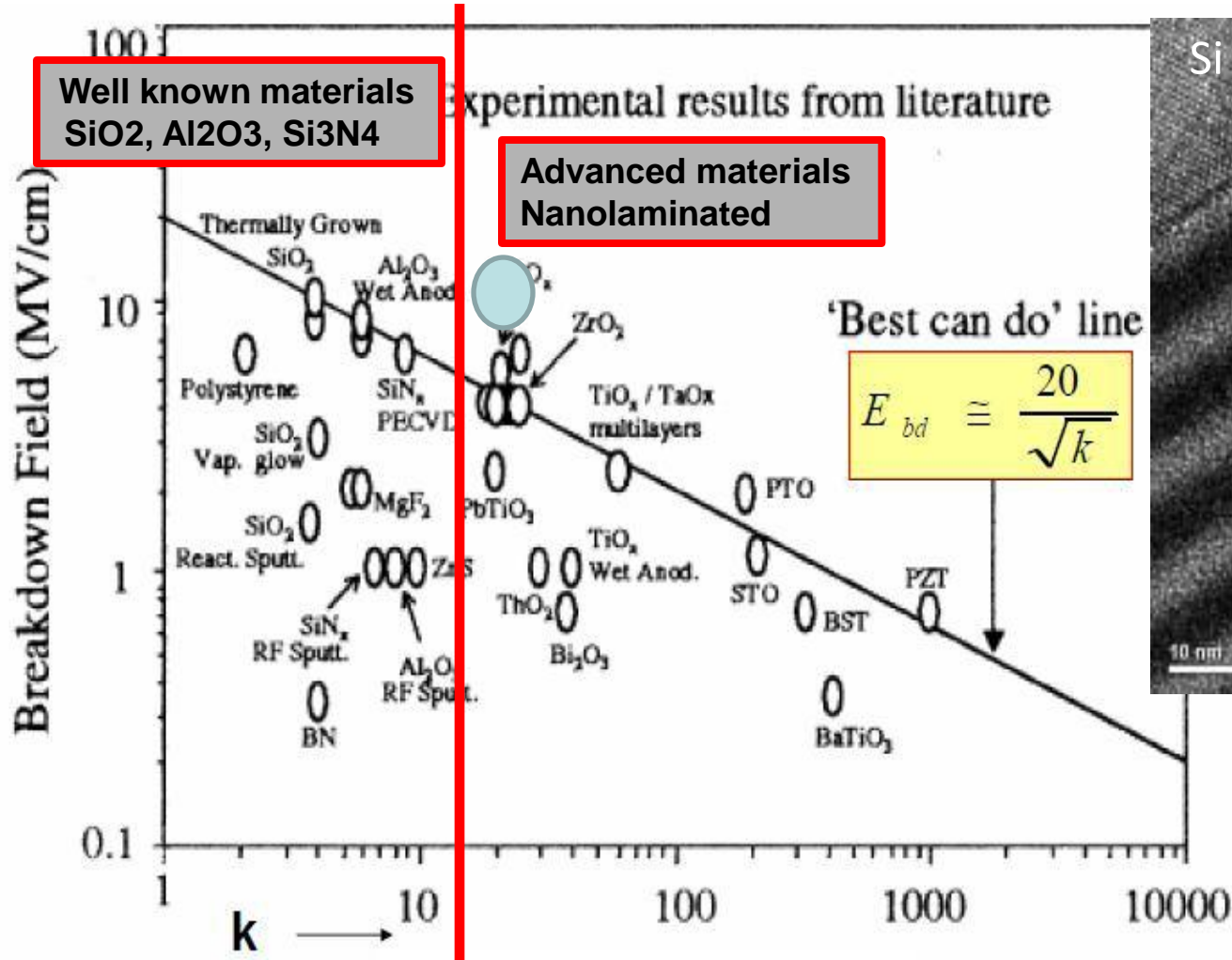
# Key features for highly integrated capacitors :The deep Silicon etching



**Tripod shape**

**with Aspect Ratio up to 60**

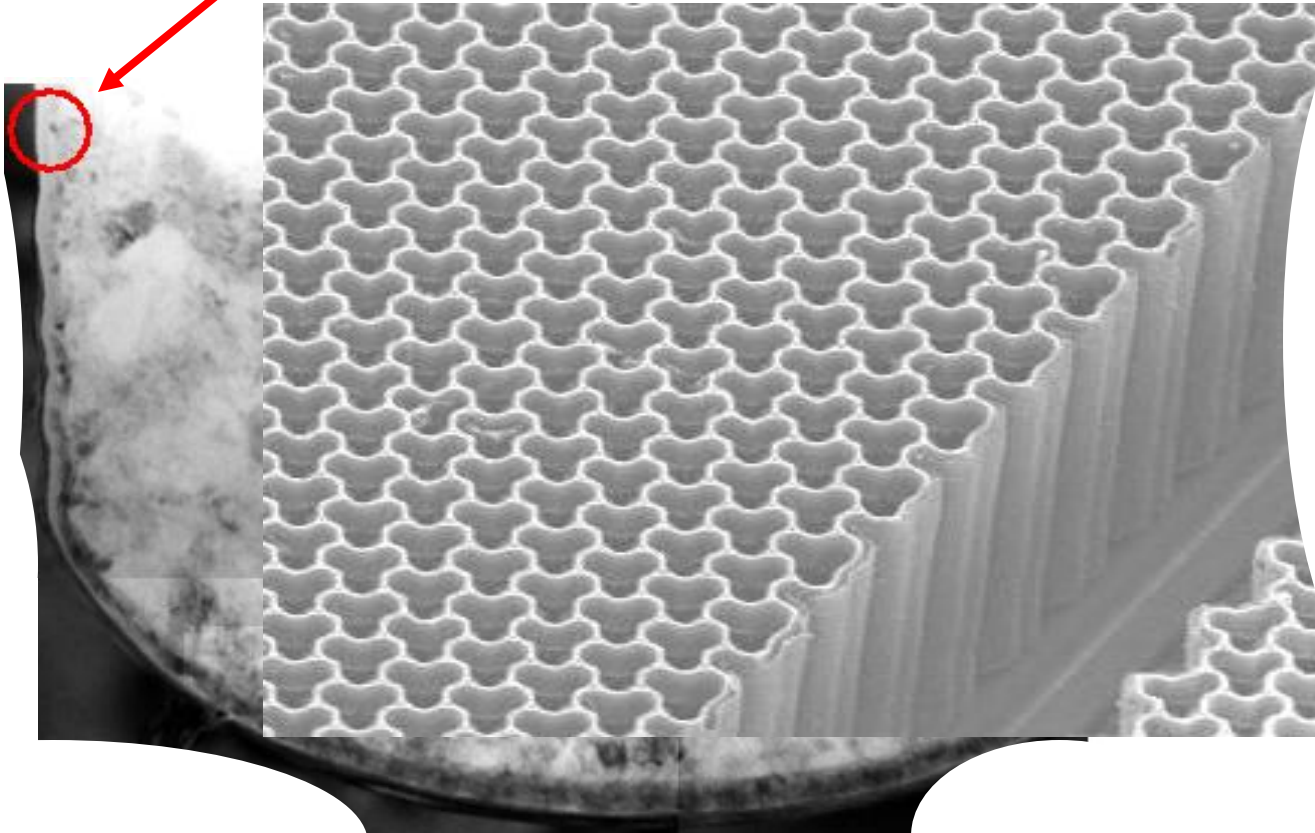
# Key features for highly integrated capacitors : The dielectric



Relative permittivity as a function of Breakdown field

# Key features for highly integrated capacitors : The dielectric deposition

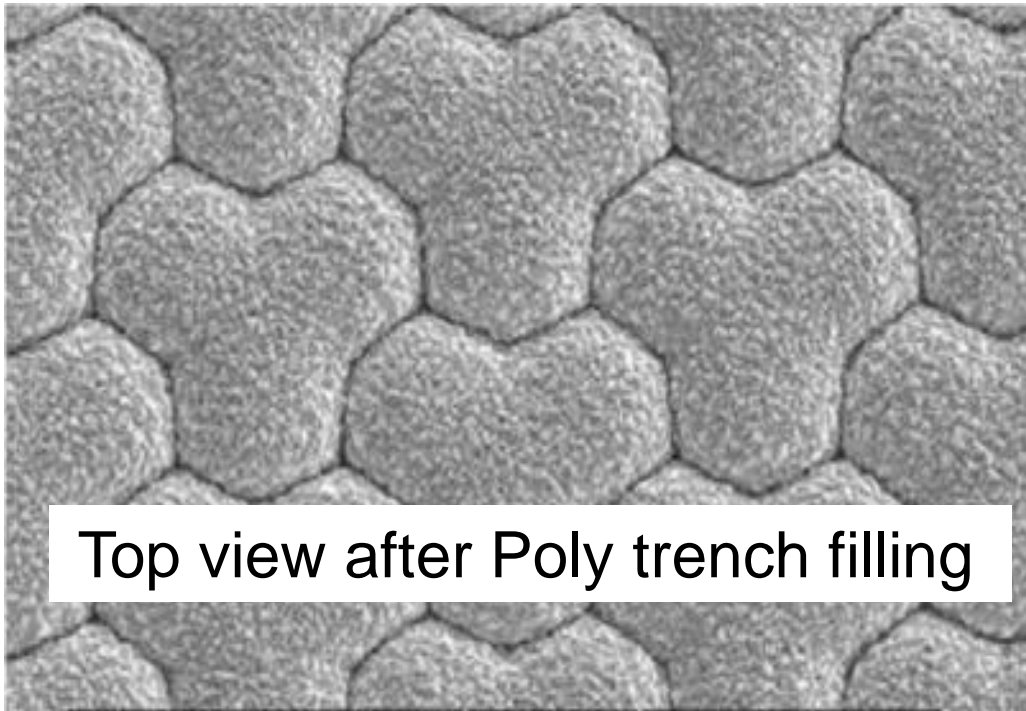
Step coverage is key !





# Key features for highly integrated capacitors :

## The trenches filling and the thermal budget seen by the 3D structures



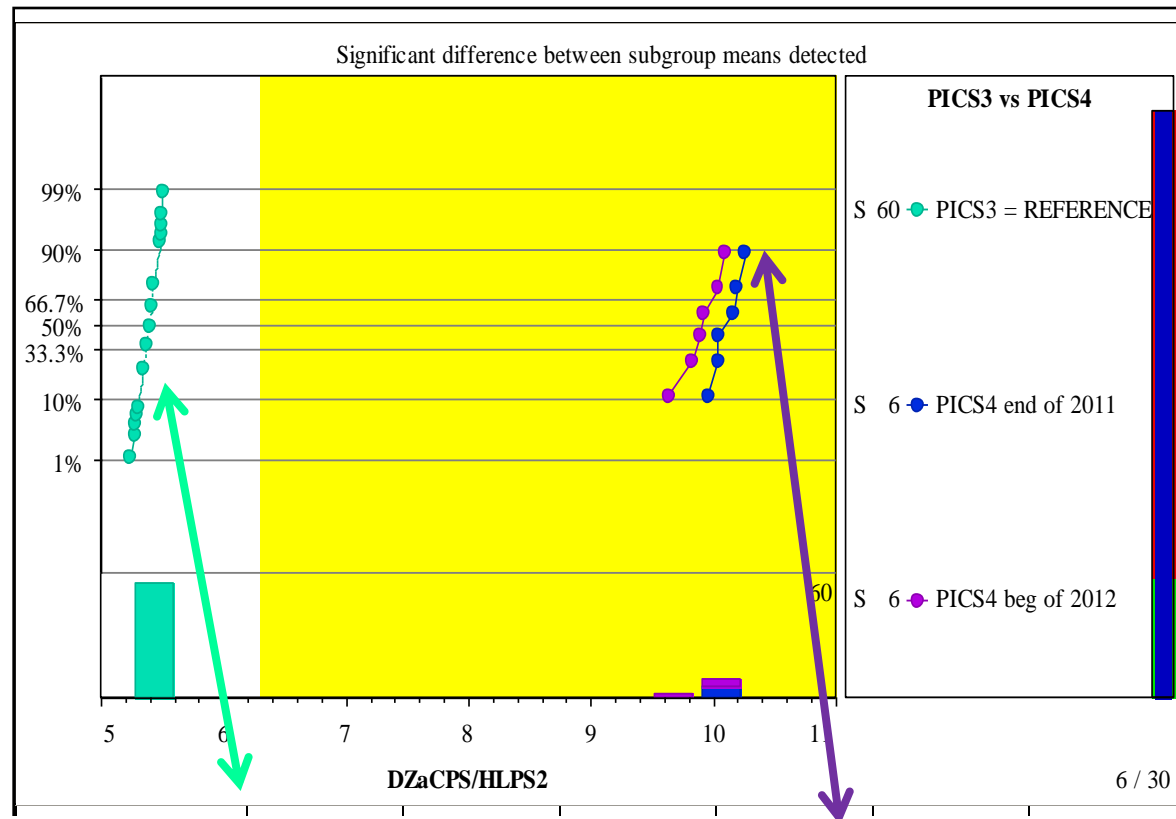
Top view after Poly trench filling

# PICS4 characterization

- Batches were characterized at PCM level (Process Control Modules)
- Investigated parameters are those corresponding to leakage through the dielectric, capacitance density and also breakdown voltage for both 2D and 3D capacitors
- Results were obtained from Keithley (raw PCM results).
- Two sets of measurements

# PICS4 characterization

2D **capacitor densities** of the PICS4 wafers compared to a PICS3 reference batch :



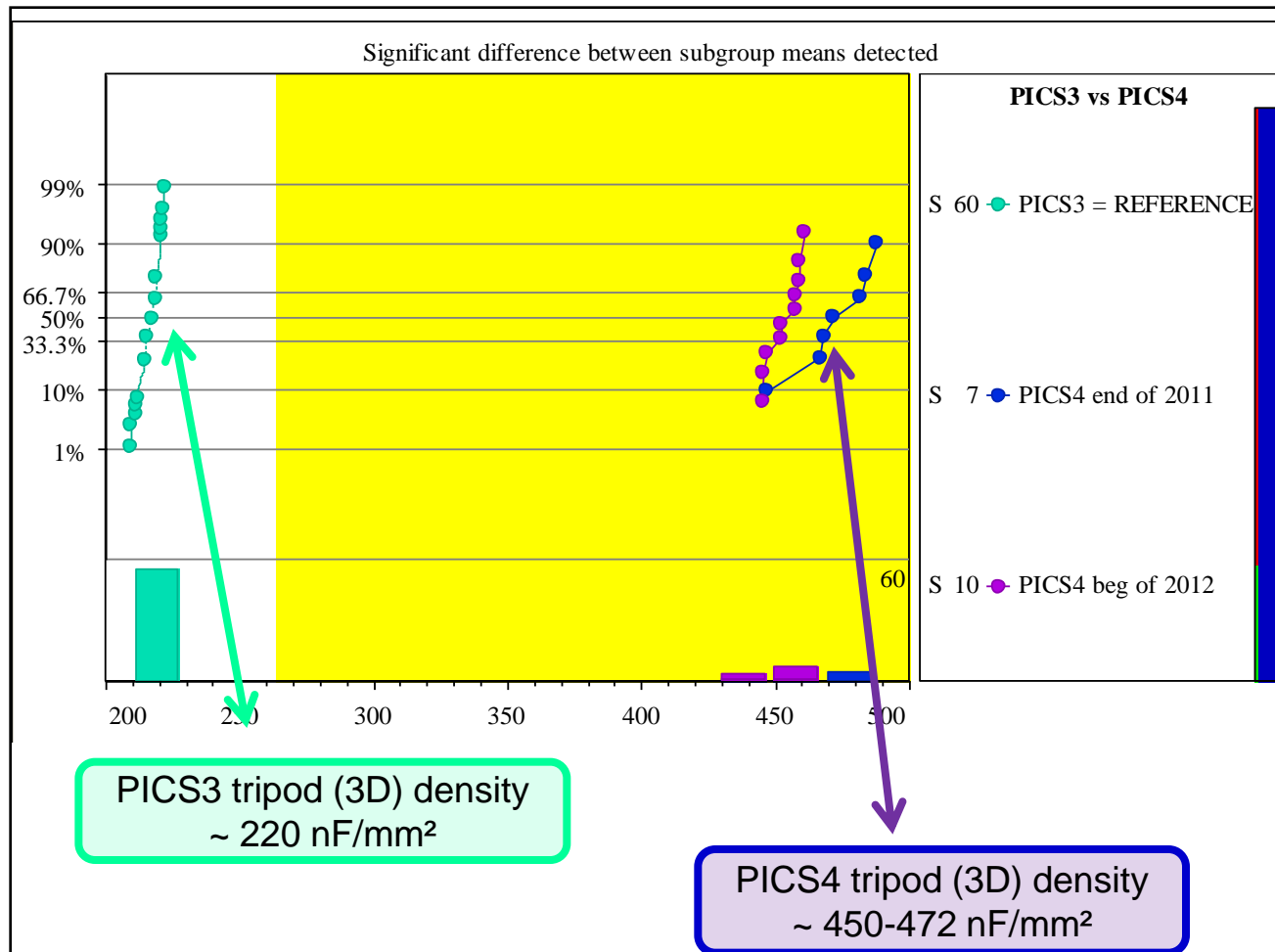
PICS3 planar (2D) density  
~ 5.4 nF/mm<sup>2</sup>

PICS4 planar (2D) density  
~ 10.0 nF/mm<sup>2</sup>



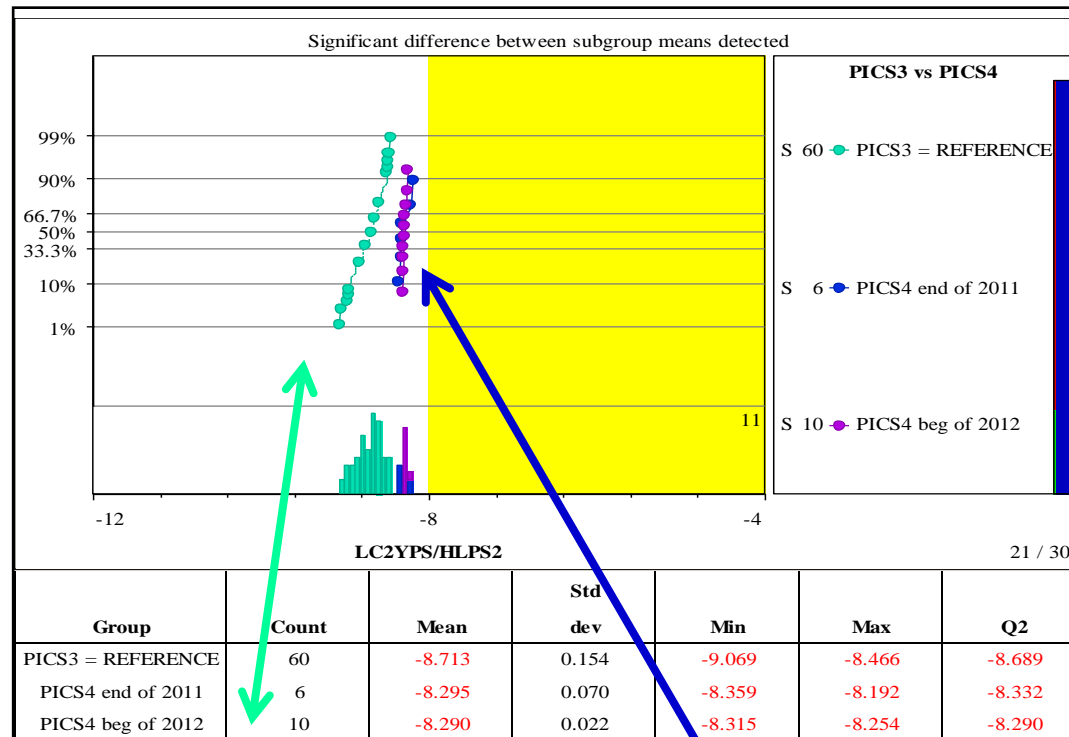
# PICS4 characterization

3D **capacitor densities** of the PICS4 wafers compared to a PICS3 reference batch :



# PICS4 characterization

3D **capacitor leakage** of the PICS4 wafers compared to a PICS3 reference batch :

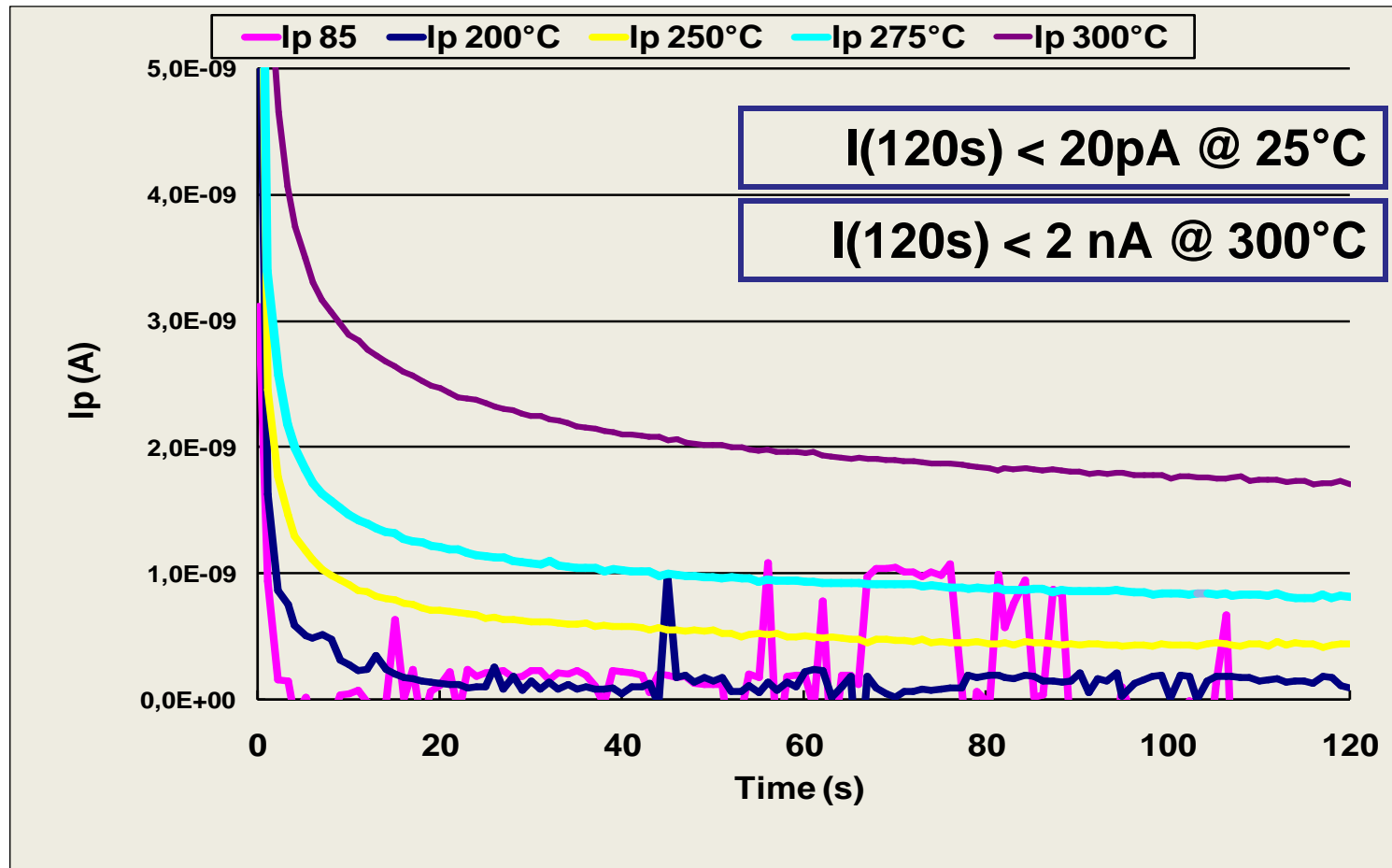


PICS3 tripod (3D) leakage ~ -8.7 logA

PICS4 tripod (3D) leakage ~ -8.3 logA

# DC leakage current at high Temperature

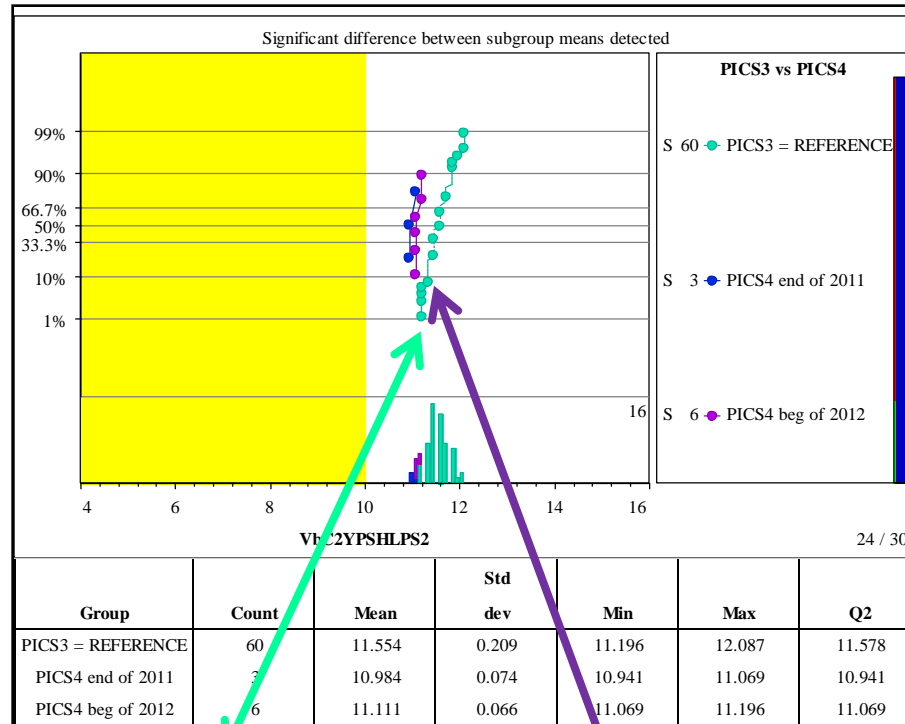
C= 100nF (Amps @ 3V)





# PICS4 characterization

3D (CAPY) capacitor  $V_{BD}$  of the PICS4 wafers compared to a PICS3 reference batch :



PICS3 tripod (3D)  
VBD ~ 11.6 V

PICS4 tripod (3D)  
VBD ~ 11V

# PICS4 characterization

- Capacitance density calculation at PCM level is impacted by the area required to connect to the electrodes.
- As a consequence, PCM densities are lower than the density measured on the products.
- The real capacitance densities are the following :
  - 2D = 11.40nF/mm<sup>2</sup> in PICS4 (6.15nF/mm<sup>2</sup> in PICS3 on the ref batch)
  - 3D = 542.44nF/mm<sup>2</sup> in PICS4 (243.96nF/mm<sup>2</sup> in PICS3 on the ref batch)

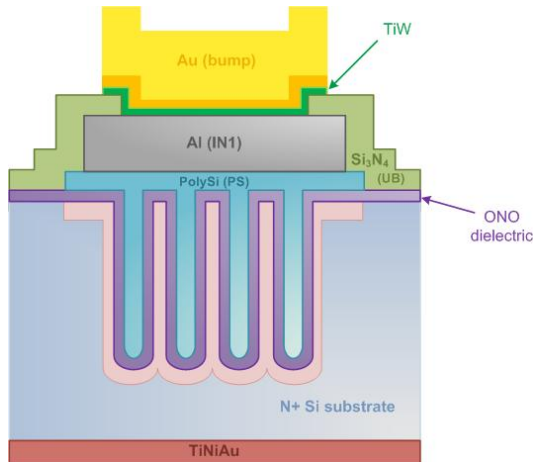


# **PICS High Voltage**

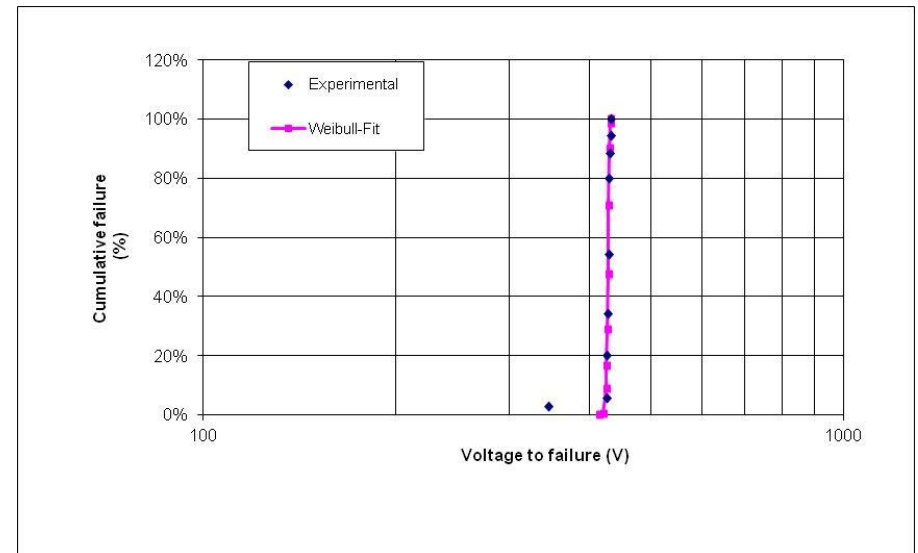
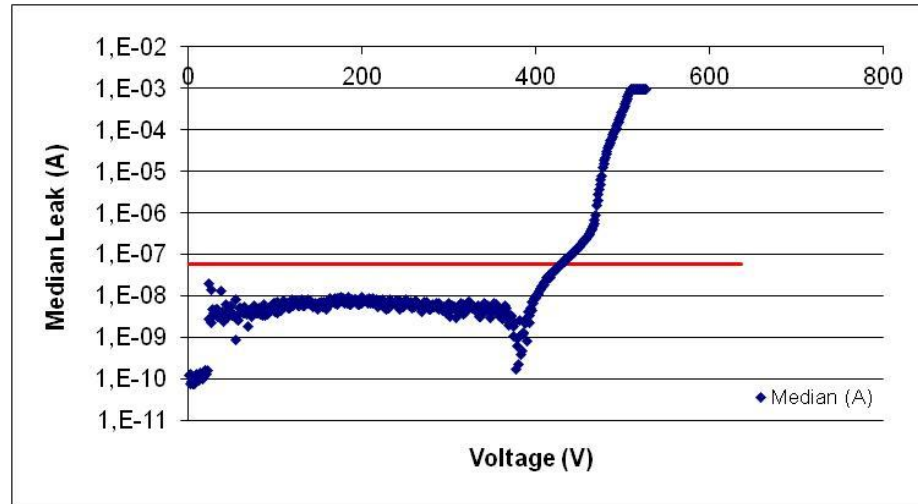
# PICS High Voltage

Larger pores to introduce a thicker dielectric  
Deeper pores to keep high capacitance density

$$C=1.35\text{nF/mm}^2$$



V<sub>use</sub> = 421 V (0.1% cumulative failure) at room temperature





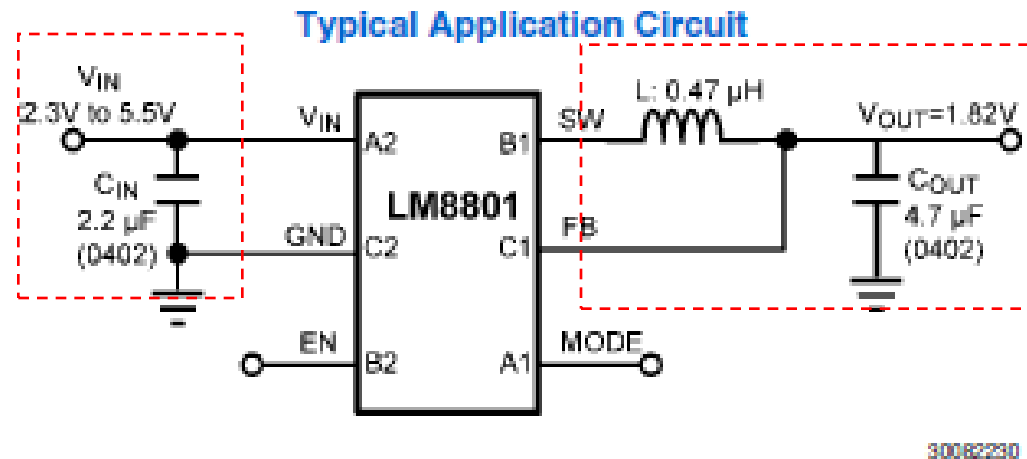


# Examples of application

# DCDC converter

## LM8801 overview\*

\* Courtesy NationalSemi. see application brochure for details



### Inductor

- Current rating steady = 600mA
- Current rating max ~ 900mA
- ESR  $\leq 100\text{m}\Omega$
- $L \geq 300\text{nH}$

Small footprint : min 4.8 x 4.8 mm

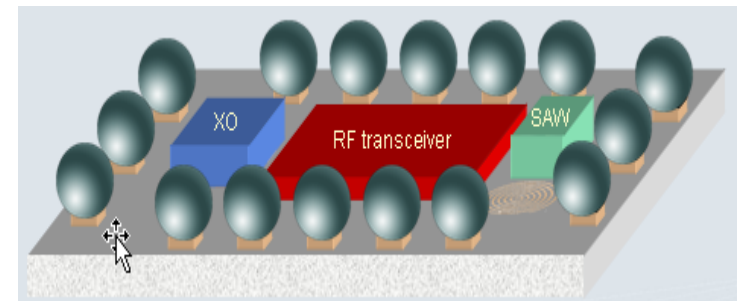
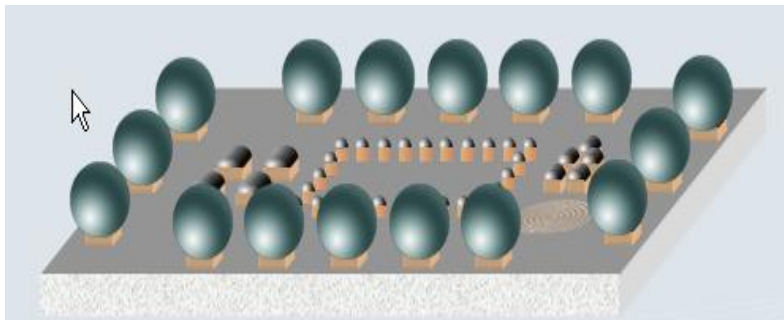
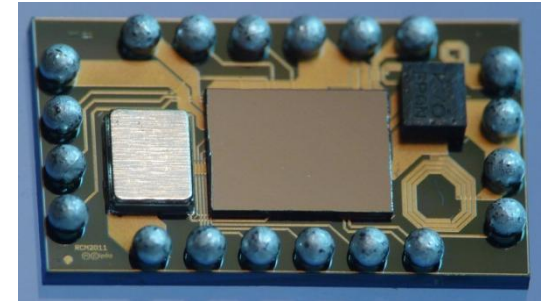
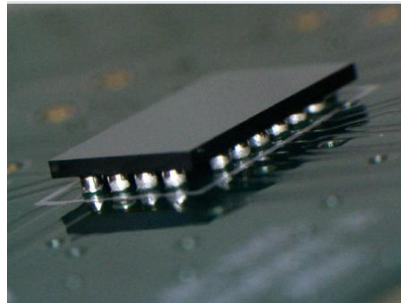
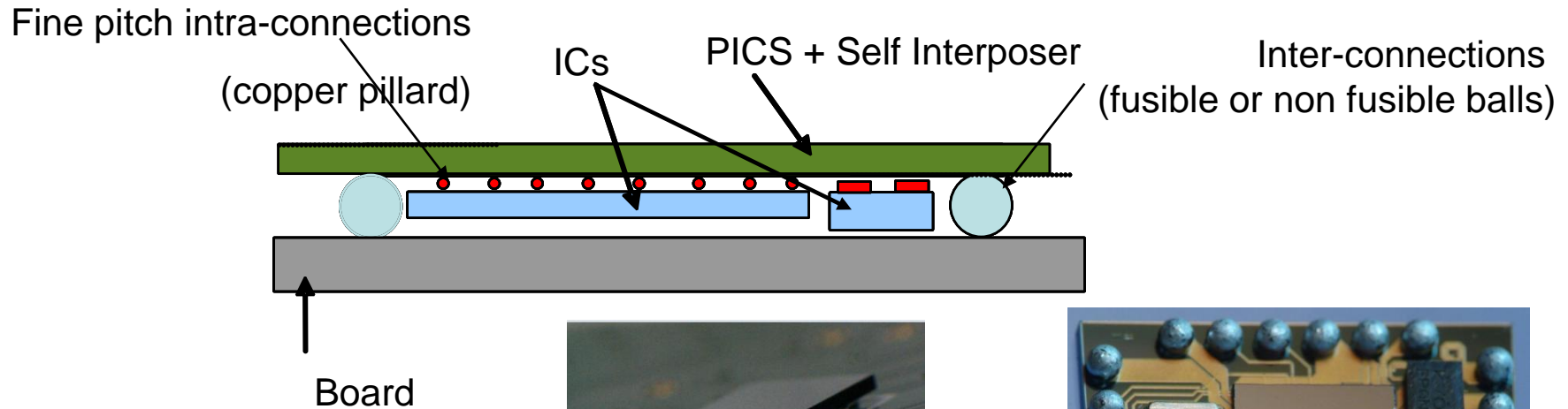
Ultra low profile : 0.35

Several assembly options : WLCSP or FlipChip

### Capacitors

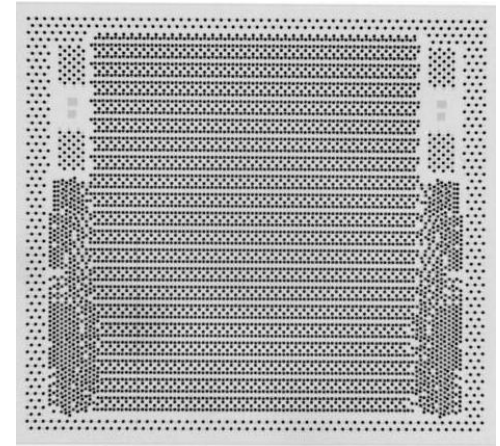
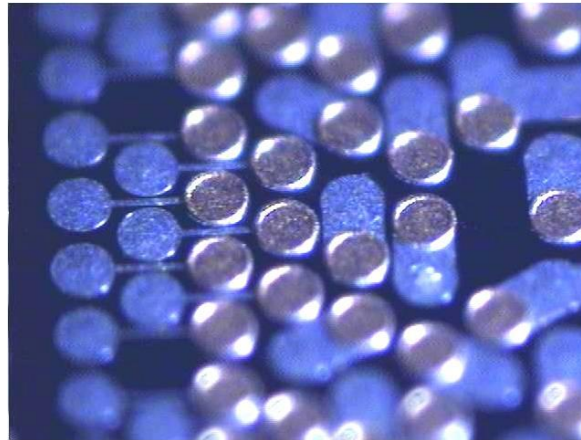
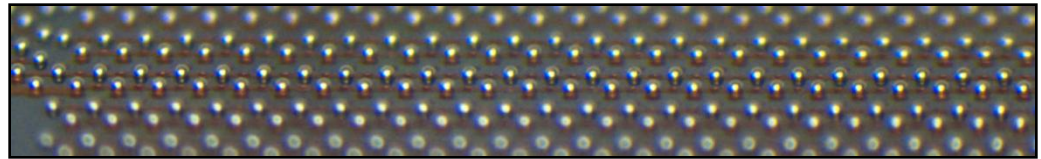
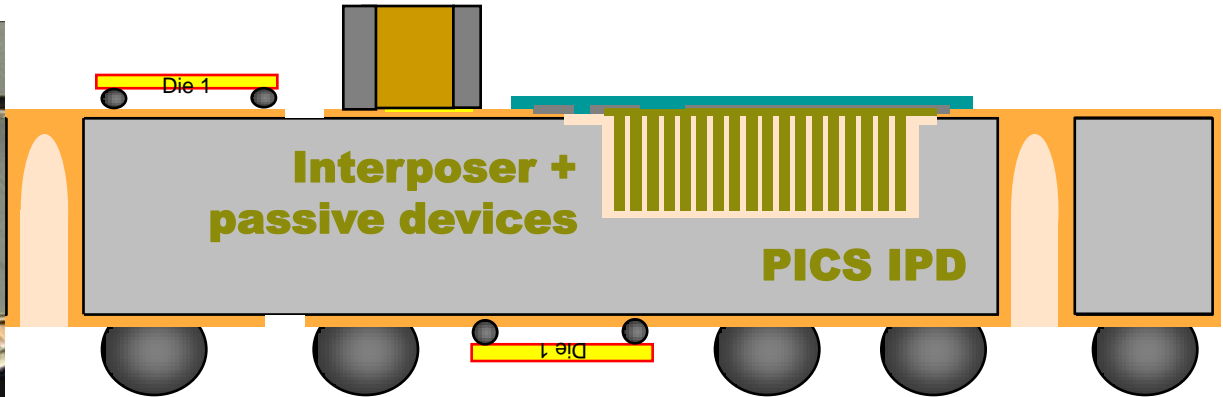
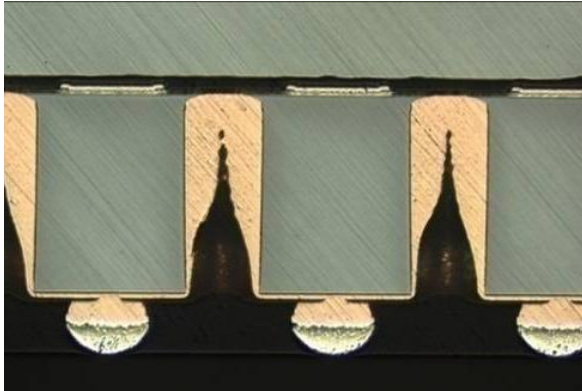
- ESR  $\leq 100\text{m}\Omega$
- $C_{out} = 4.7\mu\text{F}$
- $C_{in} = 2.2\mu\text{F}$
- Absolute Max rating = 6.3V
- Typ rating = 3.6V

# Integration capabilities with PICS





# Through Silicon Vias





# Conclusion



# Conclusion

IPDIA 3D Silicon Capacitor is offering many advantages :

- ✓ High capability of integration, low profile
- ✓ Very high stability with an outstanding behaviour at 250°C
- ✓ Extremely low failure rate .No burn-in test .
- ✓ Ultra Low leakage .
- ✓ High quality manufacturing process
- ✓ High flexibility

Coming soon : higher integration in the power system management thanks to higher Capacitor density !



[www.ipdia.com](http://www.ipdia.com)